

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-319884
 (43)Date of publication of application : 16.11.2001

(51)Int.CI. H01L 21/205
 B01J 19/08
 C23C 16/511
 H01L 21/3065
 H01Q 13/10
 H01Q 21/20
 H05H 1/46

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(54) PLASMA PROCESSING SYSTEM

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a plasma processing system having a relatively simple structure.
SOLUTION: A plasma is generated by introducing high frequency power into an evacuated container 22 and an object W to be processed is subjected to a specified processing using the plasma. In such a plasma processing system, a dipole antenna 42 is provided at the ceiling of the processing container in order to introduce high frequency power into the container. According to the arrangement, the structure is simplified relatively.

